Started on	Tuesday, 3 September 2024, 10:35 PM
State	Finished
Completed on	Tuesday, 3 September 2024, 10:36 PM
Time taken	27 secs
Marks	4.00/4.00
Grade	**10.00** out of 10.00 (**100**%)

Question 1

Correct

Mark 1.00 out of 1.00

Which of the following statements are correct about the configuration of the electrodes in a sputtering system used for the deposition of metals on semiconductor wafers?

- [ ] a. For sputtering of the metal, the metal target is biased as the anode.
- [ ] b. For sputter cleaning of the wafer, the wafer is biased as the anode.
- [x] c. For sputter cleaning of the wafer, the wafer is biased as the cathode. ✓
- [x] d. For sputtering of the metal, the metal target is biased as the cathode. ✓

Your answer is correct.

The correct answers are: For sputtering of the metal, the metal target is biased as the cathode. , For sputter cleaning of the wafer, the wafer is biased as the cathode.

Question 2

Correct

Mark 1.00 out of 1.00

Typical VLSI plasma processes are conducted in which of the plasma regimes?

- [ ] a. Breakdown
- [x] b. Abnormal glow ✓
- [ ] c. Arc
- [ ] d. Normal glow

Your answer is correct.

The correct answer is: Abnormal glow

Question 3

Correct

Mark 1.00 out of 1.00

Which of the following statements are correct about the voltage drop in different regions in the plasma in a parallel plate plasma system?

- [ ] a. The highest voltage drop in the system is in the anode sheath or dark space.
- [x] b. The highest voltage drop in the system is in the cathode sheath or dark space. ✓
- [x] c. The potential drop in the plasma is nearly zero. ✓

Your answer is correct.

The correct answers are: The highest voltage drop in the system is in the cathode sheath or dark space., The potential drop in the plasma is nearly zero.

Question 4

Correct

Mark 1.00 out

Magnetron sputtering is widely used for deposition of metals in IC manufacturing. Which of the following statements about magnetron sputtering are correct?

- [x] a. Megnetron sputtering has higher deposition rate compared to non magnetron sputtering. ✓
- [ ] b. Megnetron sputtering has lower deposition rate compared to non magnetron sputtering.

Your answer is correct.

The correct answer is: Megnetron sputtering has higher deposition rate compared to non magnetron sputtering.

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